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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/589,382	08/15/2006	Toshiyuki Ogata	1608-6 PCT/US	6030
23869 7590 G44032908 HOFFMANN & BARON, LLP 6900 JERICHO TURNPIKE			EXAMINER	
			LEE, SIN J	
SYOSSET, NY	11791		ART UNIT	PAPER NUMBER
			1795	
			MAIL DATE	DELIVERY MODE
			04/03/2008	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

## Application No. Applicant(s) 10/589 382 OGATA ET AL. Office Action Summary Examiner Art Unit Sin J. Lee 1795 -- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --Period for Reply A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS. WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION. Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b). Status 1) Responsive to communication(s) filed on 15 August 2006. 2a) This action is FINAL. 2b) This action is non-final. 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213. Disposition of Claims 4) Claim(s) 1-11 is/are pending in the application. 4a) Of the above claim(s) \_\_\_\_\_ is/are withdrawn from consideration. 5) Claim(s) \_\_\_\_\_ is/are allowed. 6) Claim(s) 1-11 is/are rejected. 7) Claim(s) \_\_\_\_\_ is/are objected to. 8) Claim(s) \_\_\_\_\_ are subject to restriction and/or election requirement. Application Papers 9) The specification is objected to by the Examiner. 10) The drawing(s) filed on is/are; a) accepted or b) objected to by the Examiner. Applicant may not request that any objection to the drawing(s) be held in abevance. See 37 CFR 1.85(a). Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152. Priority under 35 U.S.C. § 119 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some \* c) None of: Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). \* See the attached detailed Office action for a list of the certified copies not received. Attachment(s)

1) Notice of References Cited (PTO-892)

Paper No(s)/Mail Date 8/15/2006.

Notice of Draftsperson's Patent Drawing Review (PTO-948)

Interview Summary (PTO-413)
Paper No(s)/Mail Date. \_\_\_\_\_.

6) Other:

5) Notice of Informal Patent Application

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## DETAILED ACTION

## Claim Rejections - 35 USC § 103

- The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- Claims 1-9 and 11 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ota et al (JP 11-109613 and its machine-assisted English translation provided by JPO) in view of Bingel (5,739,376).

Ota teaches a positive photoresist composition containing a fullerene derivative soluble in a solvent for a resist, a photoacid generator and an acid-labile resin. Ota also teaches a negative photoresist composition containing a fullerene derivative, a photoacid generator, an alkali-soluble resin and a crosslinking compound (see abstract of the English translation). Ota also teaches the use of organic solvent (see [0072] of English translation) as well as various additive agents such as acid diffusion controlling agent (see [0070] of English translation). Ota teaches present pattern-forming method (see [0073] of English translation).

Ota teaches ([0011]) the following fullerene derivative;

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For this compound, present "n" would be 1 and thus does not teach present "n" value of two or more. Bingel teaches (col.1, lines 38-45, lines 55-63, col.2, lines 25-27, col.3, lines 34-50) the equivalence of a fullerene derivative having one malonic ester residue and a fullerene derivative having two or more malonic ester residues in terms of solubility. Based on this teaching of equivalency, it would have been obvious to one skilled in the art to obtain Ota's fullerene derivative having two or more malonic ester residues. Thus, Ota in view of Bingel would render obvious present inventions of claims 1-9 and 11.

 Claim 10 is rejected under 35 U.S.C. 103(a) as being unpatentable over Ota et al (JP 11-109613 and its machine-assisted English translation provided by JPO) in view of Bingel (5,739,376) as applied to claim 1 above, and further in view of Sato et al (6,159,652).

Although Ota in view of Bingel does not teach present organic carboxylic acid, use of such compound in a photoresist composition is already known in the art to provide high sensitivity and high resolution for the composition. See Sato, col.10, lines 57-64. Thus, it would have been obvious to one skilled in the art to use an organic carboxylic acid in Ota's photoresist composition in order to provide high sensitivity and

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high resolution. Therefore, Ota in view of Bingel would render obvious present invention of claim 10.

4. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Sin J. Lee whose telephone number is 571-272-1333. The examiner can normally be reached on Monday-Friday from 9:00 am EST to 5:30 pm EST.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Cynthia Kelly, can be reached on 571-272-1526. The fax phone number for the organization where this application or proceeding is assigned is **571-273-8300**.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

/Sin J. Lee/ Primary Examiner, Art Unit 1795 March 30, 2008